

## ABSTRACT OF THE DISCLOSURE

The present invention provides an exposure apparatus that can satisfactorily perform a measurement process and can accurately perform an exposure process, even if a liquid immersion method is applied to a twin stage type exposure apparatus. An

5 exposure apparatus (EX) comprises: two substrate stages (PST1, PST2) each capable of holding and moving a substrate (P); an exposure station (STE) that exposes, through a projection optical system (PL) and a liquid (LQ), the substrate (P) held by one substrate stage (PST1); and a measuring station (STA) that measures the substrate (P) held by the other substrate stage (PST2) or the abovementioned substrate stage (PST2); and wherein,

10 the measurement performed at the measuring station (STA) is performed in a state wherein the liquid (LQ) is disposed on the substrate stage (PST2) or the substrate (P).